

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	((carbon near silicon near oxide) SiOCH) with methylsilsequioxane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 14:58
L2	15	((carbon near silicon near oxide) SiOCH) and methylsilsequioxane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 14:58
S1	0	(carbon near silicon near oxide) with ((silicon Si) near CH2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 13:37
S2	0	(carbon near silicon near oxide) and ((silicon Si) near CH2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 13:35
S3	0	(carbon near silicon near oxide) and ((silicon Si) near CH\$1 near bond\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 13:36
S4	364	(carbon near silicon near oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 13:41
S5	82	((silicon Si) near CH\$1 near bond\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 11:01
S6	3	SiOCH with ((silicon Si) near CH\$1 near bond\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 13:37
S7	535	(carbon near silicon near oxide) SiOCH	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 14:55

S8	3	S7 and S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 13:42
S9	3	("6171770" "6329017" "6509279").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/22 14:10
S10	4	("4868336" "6074962" "6171770" "6329017").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/22 14:11
S11	6	("4868096" "6057251" "6159871" "6303192" "6303525" "6326692").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/22 14:17
S12	3	S7 and (Si near CH2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 14:40
S13	0	("2005/0006665").URPN.	USPAT	OR	ON	2005/07/22 14:40
S14	945	(Si near CH2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 14:41
S15	22	(Si near CH2 near bond)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 14:44
S16	3	S14 and S7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/22 14:44
S17	25	((silicon Si) near CH2 near bond\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 11:10
S18	948	((silicon Si) near CH2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:53

S19	3	S18 and ((carbon near silicon near oxide) SiOCH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:55
S20	14	S18 and ((insulat\$3 dielectric) near (layer\$1 film\$1))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 11:58
S21	565	S18 and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 11:53
S22	11	S21 and (silicon near oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 11:53
S23	1	((insulat\$3 dielectric) ADJ (layer\$1 film\$1)) AND carbon AND ((silicon Si) ADJ oxide) AND SiOCH AND (Si NEAR CH2) AND bond\$3.CLM.	US-PGPUB; USPAT	OR	ON	2005/07/27 12:02
S24	535	((carbon near silicon near oxide) SiOCH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:14
S25	7	S24 and CH2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:16
S26	12379	((silicon Si) near CH\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:34
S27	15	S26 and ((carbon near silicon near oxide) SiOCH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:35

S28	4947	(silicon Si) near ("CH.sub.2" CH2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:54
S29	8	S28 and ((carbon near silicon near oxide) SiOCH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 12:55
S30	8	("3615913" "3895429" "5116495" "5128737" "5205902" "5298587" "5320875" "5575929").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/27 13:03

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L1	55586	interconnect\$3 near (layer\$1 film\$1 line\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 17:55
L2	3926	1 and (interlayer near (insulat\$3 dielectric) near (layer\$1 film\$1))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 17:56
L3	900	2 and (diffus\$3 near (layer film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 17:57
L4	192	3 and damascene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 18:01
L5	149	4 and (SiO (silicon adj oxide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/27 18:01

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2799	(Cu copper) near contain\$3 near (metal Si Al Ag W Mg Be Zn Pd Cd Au Hg Pt Zr Ti Sn Ni Fe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/28 07:13
L2	187	1 and damascene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/28 07:14